

ABSTRACT OF THE DISCLOSURE

A photoresist layer is exposed two or more times. One exposure is conducted through a regular mask, and one exposure through a modified mask with a non-clear region extending beyond a convex boundary of the non-clear region of the regular mask.

- 5 The exposure through the modified mask allows one to reduce the exposure dose used with the regular mask, and thus alleviates the resist overexposure near convex areas of the non-clear pattern of the regular mask. Other embodiments are also provided.

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